



Attorney Docket :  
033082 M 119

P A T E N T

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

CONFIRMATION NO. 4442

In re the application of:

Hitoshi KATO, et al.

Serial No. : 10/066,627

Filed : February 6, 2002

Art Unit : 2822

Examiner : Maria F. Guerrero

For : A Precleaning Method of Precleaning a Silicon Nitride Film  
Forming System (as amended)

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AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

A response to the Office Action dated September 4, 2003 (Paper No. 10) was due by December 4, 2003. A Petition for Extension of Time (two months, large entity), and a check including payment of the extension fee, are enclosed, extending the period for response to February 4, 2004. Therefore, please accept this Amendment as timely filed.

In response to Paper No. 10, kindly amend the above-identified patent application as set forth below.